Femtosecond-laser Microstructuring of Silicon for Novel Optoelectronic Devices

James Carey Photonics West San Jose, CA, 25 January 2005



Motivation

Silicon:

- most widely used semiconductor
- enormous infrastructure, inexpensive
- can't do everything
- alter silicon to improve functionality



apparatus



apparatus

















- maskless etching process
- self-organized, conical microstructures
- highly light absorbing

Outline

- optical properties
- structural and chemical analysis
- photodetectors
 - the p-n junction
 - femtosecond-laser microstructured silicon photodiodes
- outlook



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1/24/03

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reflectance (integrating sphere)



reflectance (integrating sphere)



transmittance (integrating sphere)



transmittance (integrating sphere)



absorptance (1 - R - T)



absorptance (1 - R - T)



What causes the near-unity absorptance?



multiple reflections enhance absorption



multiple reflections enhance absorption



electronic band structure changes



- enhanced absorption in visible
- near-unity absorption in infrared
- modified electronic band structure

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Band structure changes: defects and/or impurities.





cross-sectional Transmission Electron Microscopy

M. Wall, F. Génin (LLNL)






crystalline silicon core







- 300 nm disordered surface layer
- undisturbed crystalline below
- surface layer: polycrystalline Si with 1.6% sulfur

Microstructure with different ambient gases:

- gas species incorporated into surface
- sulfur critical for below-band gap absorption













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join acceptor and donor type Si...



join acceptor and donor type Si...



electrons and holes diffuse across junction...



...and get 'trapped' after they combine



build-up of charge leads to electric field that stops diffusion



non-conducting layer at junction



apply electric field...



...holes pushed left, electrons to right...



and so depletion zone expands



NO conduction



reverse electric field...



...depletion zone shrinks and current flows



so pn-junction like one-way valve for charge flow: a diode

depletion layer can convert light into electric energy



incident photon knocks out electron...



...creating an electron-hole pair



E-field separates eh-pair, causing current



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1/24/0.

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create photodiode using black silicon/silicon junction

lm

crystalline Si



irradiate with 100-fs laser pulses in SF₆



Cr/Au contact



cross section



Cr/Au contact



black silicon/silicon junction


IV characteristics



IV characteristics



We have a diode. What about a photodiode?

responsivity



responsivity



responsivity



black silicon/silicon photodiode

- nearly 100x larger signal in visible
- 10⁴ larger signal in near-IR
- quantum efficiency >> 1, gain!

Outlook



Appl. Phys. Lett., 82, 1715 (2003)

Outlook

- photodetectors
- microstructured surfaces
 - many types of micro- and nanostructures
 - strong field emission
 - visible photoluminescence

Appl. Phys. Lett., 85, 5694 (2004)

Outlook



Summary



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- self-organized, conical microstructures
- near-unity absorption from near-UV to near-IR
- high sensitivity VIS/NIR silicon-based photodiodes
- maskless process, easily integrated with microelectronics
- just the beginning: many promising applications

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http://mazur-www.harvard.edu/

response time: 10 ns rise, 30 ns fall



effect of annealing



effect of annealing



responsivity (white light)



Structural analysis

before annealing





after annealing





Structural analysis





annealed

annealing does not affect visible structure

Nanosecond vs femtosecond

800 nm, 100 fs, 10 kJ/m²





248 nm, 30 ns, 30 kJ/m²





Nanosecond vs femtosecond

800 nm, 100 fs, 10 kJ/m²



fs cones etched below surface

248 nm, 30 ns, 30 kJ/m²



ns cones grow above surface

ripples





laser polarization





















SF₆



- 1. Interference ripples $(\perp \text{ to polarization})$
- 2. Coarsened ridges (⊥ to ripples)
- 3. Beads sharpening into spikes



$$N = 2$$

N = 4

N = 10

Two distinct wavelengths: ripples and spikes

feature intensities

SF₆ ripples



parallel

perpendicular

feature intensities

SF₆ spikes



parallel

perpendicular
Formation process



- spike wavelength appears as ripple wavelength disappears
- spike wavelength appears first perpendicular to polarization

N = 10

What sets the length scales?

- ripples: laser wavelength
- ridges and spikes: perhaps capillary waves

Capillary wavelength set by melt depth, duration

$$\lambda = \left[\frac{\sigma d}{\rho}\right]^{\frac{1}{4}} (2\pi\tau)^{\frac{1}{2}}$$

- longest wavelength similar to spike spacing (10 µm)
- both spike spacing and capillary wavelength increase with laser fluence

Structural and chemical analysis

microstructured in different gases



doping



ion implanted/laser annealed



annealing



fluence

